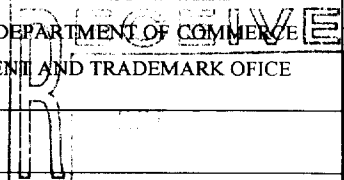


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10-27-1999



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To the Honorable Commissioner of Patents and

s or copy thereof.

1. Name of conveying party(ies):

Filplas Vacuum Technology Pte Ltd.

Additional name(s) of conveying party(ies) attached? yes no

2. Name and address of receiving party(ies):

Name: Nanofilm Technologies International Pte Ltd.

Address: Innovation Centre 18 Nanyang Drive,
Block 2 Unit 233
Nanyang Technological University
Singapore 637723

City: State: ZIP:

Additional name(s) & address(es) attached? yes no

3. Nature of conveyance:

 Assignment Merger

 Security Agreement Change of Name

 Other License Agreement _____

Execution Date: August 3, 1999

4. Application number(s) or patent number(s):

If this document is being filed together with a new application, the execution date of the application is:

A. Patent Application No.(s) B. Patent No.(s)

08/894,420; 08/894,419; and 09/236,113

Additional numbers attached? yes no

5. Name and address of party to whom correspondence concerning document should be mailed:

Name: Bruce S. Londa
Internal Address: Londa and Traub LLP
Street Address: 20 Exchange Place, 37th Floor
City: New York State: New York ZIP: 10005

3075.00001

6. Total number of applications and patents involved:
3

7. Total fee (37 CFR 3.41)..... \$ 120.00
 Enclosed
 Authorized to be charged to deposit account

8. Deposit account number: 04-2216

(attach duplicate copy of this page if paying by deposit account)

DO NOT USE THIS SPACE

9. Statement and signature.
To the best of my knowledge and belief, the foregoing information is true and correct and any attached copy is a true copy of the original document.

Bruce S. Londa *[Signature]* October 21, 1999
Name of Person Signing Signature Date
(PTO Reg. No. 33,531)

Total number of pages including cover sheet, attachments and document: 5

10/26/1999 MTHAI1 00000314 042216 08894420
01 FC:581 120.00 CH



Professor Yeong Hin Yuen
Director
Filplas Vacuum Technology Pte Ltd

<u>Clause</u>	<u>Contents</u>
Definitions	<p>(i) "Licensor" is defined as Filplas Vacuum Technology Pte Ltd;</p> <p>(ii) "Licensee" is defined as Nanofilm Technologies International Pte Ltd;</p> <p>(iii) "Processes" means the process or method of manufacturing the Sources, Systems and Products utilising the Filtered Cathodic Arc Source ("FCAS") technology under the Patents;</p> <p>(iv) "Products" means the products which are synthesised by thin film coatings utilising the Processes or any FCAS technology under the Patents, which products are limited to be used only for or in Exclusive Applications or Non-exclusive Applications, as the case may be;</p> <p>(v) "Sources" means the equipment which is manufactured using the Processes or any FCAS technology under the Patents and used for the purpose of manufacturing Products;</p> <p>(vi) "Systems" means the complete or partial machines incorporating a single or multiple number of Sources used for the purpose of manufacturing Products;</p> <p>(vii) "Optical Applications" means the applications in which the technology is used to apply coatings to lenses, prisms, filters or mirrors whether manufactured from glass or any other material or any other application within a system, the principal object of which is to handle the transmission or reflection of light in all wavelengths including the visible spectrum, infra-red (IR), ultraviolet (UV) and lasers</p> <p>(viii) "Patents" means:-</p> <p>(a) the patent applications short particulars whereof are set out in Schedule 1;</p> <p>(b) all patent applications that may hereafter be filed in the Territory or part thereof by or on behalf of the Licensor which either are based on or claim priority from any of the foregoing patent applications; and</p> <p>(c) all patents which may be granted pursuant to any of the foregoing patent applications</p> <p>(ix) "Term" means the period during which the Agreement is in force, in accordance with Clause 12</p> <p>(x) "Territory" means every or any country, state and city in the world</p>

Clause Contents

2.1 Licensor hereby grants to the Company a licence (the "Licence") to use the Patents on the terms and conditions set forth herein. The Company shall have the right to use the Patents to operate the Processes for the purposes of the design, manufacture, distribution, supply and sale of the Sources, Systems and Products other than for Optical Applications, in the Territory during the Term of this Agreement.

2.2 The Licence shall be exclusive to the Company in respect of the:-

- (i) design, manufacture, distribution, supply and sale of the Sources; and
- (ii) design, manufacture, distribution, supply and sale of the Products used for or in relation to magnetic data storage applications including carbon coatings for sliders and media in hard disk drive applications.

The above applications shall be referred to as "Exclusive Applications".

2.3 The Licence shall be non-exclusive to the Company in respect of the:-

- (i) design, manufacture, distribution, supply and sale of the Systems; and
- (ii) design, manufacture, distribution, supply and sale of the Products for all applications other than for magnetic data storage and Optical Applications.

The above applications shall be referred to as "Non-exclusive Applications".

12.1, 12.2 Unless terminated earlier in accordance with the following provisions, this Agreement shall be in force until 31 March 2004.

The Agreement may be extended for a further period of five (5) years by the Company upon six (6) months' notice to Licensor prior to the expiration of the Agreement...

**SCHEDULE 1
PATENTS**

<u>No.</u>	<u>Application No.</u>	<u>Country Filed</u>	<u>Date Filed</u>	<u>Brief Title of Invention</u>
1.	GB 9503305.6	United Kingdom	20 February 1995	Filtered Cathodic Arc Source
	WO PCT/GB96/00389	PCT	20 February 1996	
	EP 96903119.4	European Patent Office	20 February 1996	
	US 08/894 420	United States	20 February 1996	
	SG 9704281-6	Singapore	20 February 1996	
	and all patent applications applied and patents registered in respect of this invention.			
2.	GB 9503304.9	United Kingdom	20 February 1995	Deposition Apparatus
	WO PCT/GB96/00390	PCT	20 February 1996	
	EP 96903120.2	European Patent Office	20 February 1996	
	US 08/894 419	United States	20 February 1996	
	SG 9704279-0	Singapore	20 February 1996	
	and all patent applications applied and patents registered in respect of this invention.			
3.	GB 9615548.6	United Kingdom	24 July 1996	Cathode arc source and graphite target
	WO PCT/GB97/01992	PCT	24 July 1997	
	SG 9900387-3	Singapore	24 July 1997	
	and all patent applications applied and patents registered in respect of this invention.			

PATENT

REEL: 010328 FRAME: 0958

<u>No.</u>	<u>Application No.</u>	<u>Country Filed</u>	<u>Date Filed</u>	<u>Brief Title of Invention</u>
4.	GB 9722645.0 PCT/IB98/01764	United Kingdom PCT	24 October 1997 26 October 1998	: Enhanced macroparticle filter and cathode arc source
	and all patent applications applied and patents registered in respect of this invention.			
5.	GB 9722648.4 PCT/IB98/01765	United Kingdom PCT	24 October 1997 26 October 1998	Arc monitoring
	and all patent applications applied and patents registered in respect of this invention.			
6.	GB 9722649.2 PCT/IB98/01762	United Kingdom PCT	24 October 1997 26 October 1998	Cathode arc source for metallic and dielectric coatings.
	and all patent applications applied and patents registered in respect of this invention.			
7.	GB 9722650.0 PCT/IB98/01768	United Kingdom PCT	24 October 1997 26 October 1998	Cathode arc source with target feeding apparatus
	and all patent applications applied and patents registered in respect of this invention.			

PATENT

RECORDED: 10/25/1999

REEL: 010328 FRAME: 0959